

## Search Results -

Term	Documents
(1 SAME 5).USPT,PGPB.	80

US Patents Full-Text Database
US Pre-Grant Publication Full-Text Database

JPO Abstracts Database EPO Abstracts Database Derwent World Patents Index

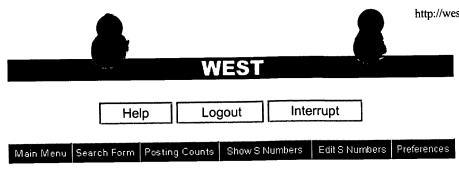
Database: IBM Technical Disclosure Bulletins

	11	same	15	国	
Refine Search:				₹	Clear

## **Search History**

**Today's Date: 10/31/2001** 

DB Name	Query		Set Name	
USPT,PGPB	11 same 15	80	<u>L6</u>	
USPT,PGPB	(hydrogen peroxide or "H.sub.2 O.sub.2" or "H2O2")	57154	<u>L5</u>	
USPT,PGPB	13 and @pd<19970214	27	<u>L4</u>	
USPT,PGPB	11 same (ozone or "O.sub.3")	52	<u>L3</u>	
USPT,PGPB	11 and @pd<19970214	2264	<u>L2</u>	
USPT,PGPB	((((remov\$3 or etch\$3 or contact\$3 or clean\$3 or eliminat\$3) same (polymer\$2 or resin or photoresist or resist or organic) )same (substrate or wafer or semiconductor or electronic or circuit)) same ((acetic acid or "CH.sub.3 COOH" or ethanoic adj2 acid or vinegar acid or methane near carboxylic acid or acetate or carbonate or phosphonic acid)))	3395	<u>L1</u>	



## Search Results -

Term	Documents
@PD.USPT,PGPB.	6831961
(7 AND (@PD < "19970214")).USPT,PGPB.	27

US Patents Full-Text Database
US Pre-Grant Publication Full-Text Database
JPO Abstracts Database

Database:

EPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

17 and @pd<19970214  Refine Search:	Clear
Search History	i de vide de la compania del compania del compania de la compania del compania del compania de la compania del compania de

Today's Date: 10/31/2001

DB Name	<b>Query</b>	Hit Count	Set Name
USPT,PGPB	17 and @pd<19970214	27	<u>L8</u>
USPT,PGPB	14 same (ozone or "O.sub.3")	52	<u>L7</u>
USPT,PGPB	15 and @pd<19970214	85	<u>L6</u>
USPT,PGPB	14 and ((134/\$)!.CCLS.)	151	<u>L5</u>
USPT,PGPB	12 same 13	3395	<u>L4</u>
USPT,PGPB	(acetic acid or "CH.sub.3 COOH" or ethanoic adj2 acid or vinegar acid or methane near carboxylic acid or acetate or carbonate or phosphonic acid)	393082	<u>L3</u>
USPT,PGPB	11 same (substrate or wafer or semiconductor or electronic or circuit)	86301	<u>L2</u>
USPT,PGPB	(remov\$3 or etch\$3 or contact\$3 or clean\$3 or eliminat\$3) same (polymer\$2 or resin or photoresist or resist or organic)	399505	<u>L1</u>